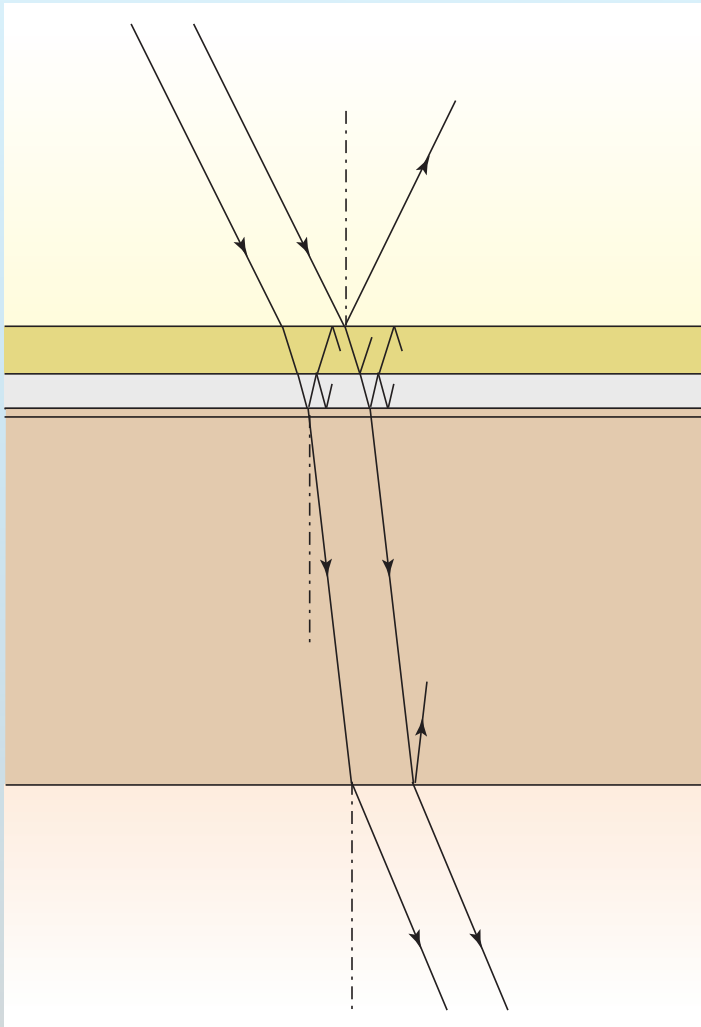


qe\_max\_bigprint.eps

PROLOGUE: At the SDW meeting here in 1999, Jim Beletic asked for a show of hands ---



“How accurately do you think you can measure the quantum efficiency of a CCD ?”

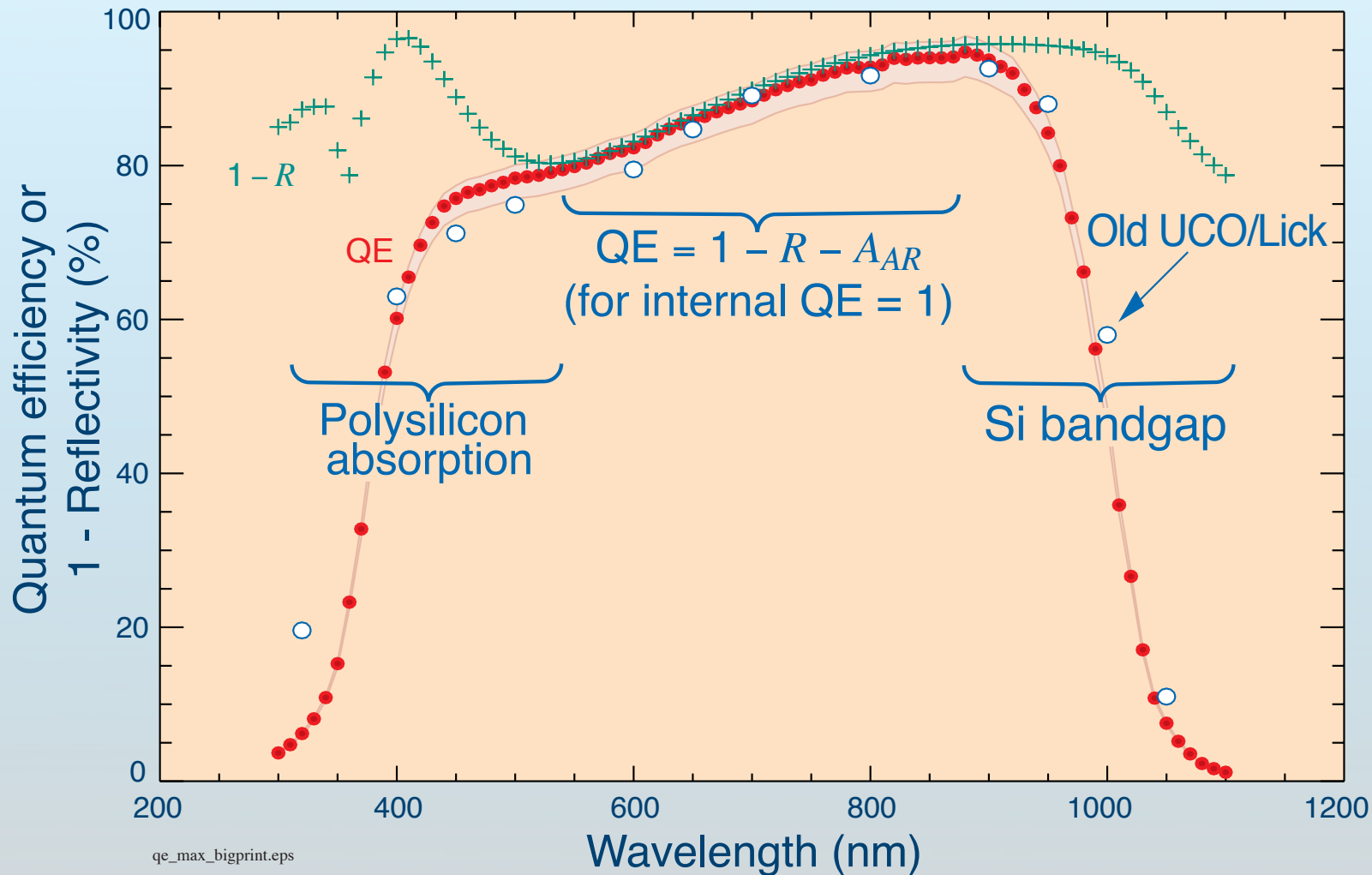
\* 10% ?

\* 5% ??

\* 1% ??

Successively fewer hands went up

Since then we've learned to measure the reflectivity, which can be done absolutely and easily. ( $R$  doesn't depend on a standard PD!)  
 -- and the mid-region can be used to normalize the QE measurements.



(Figure from Maximilion Fabricius' diplomathesis)

First we built the LBNL QE Machine . . .



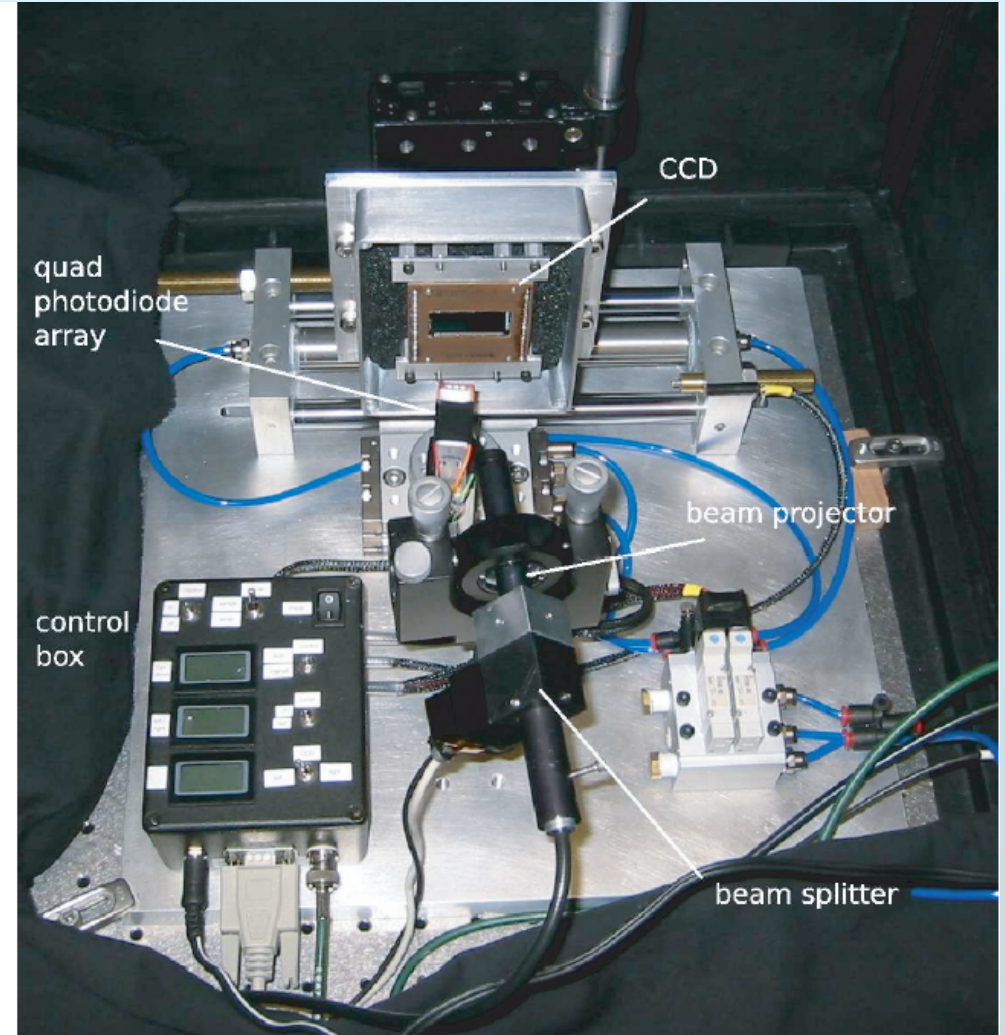
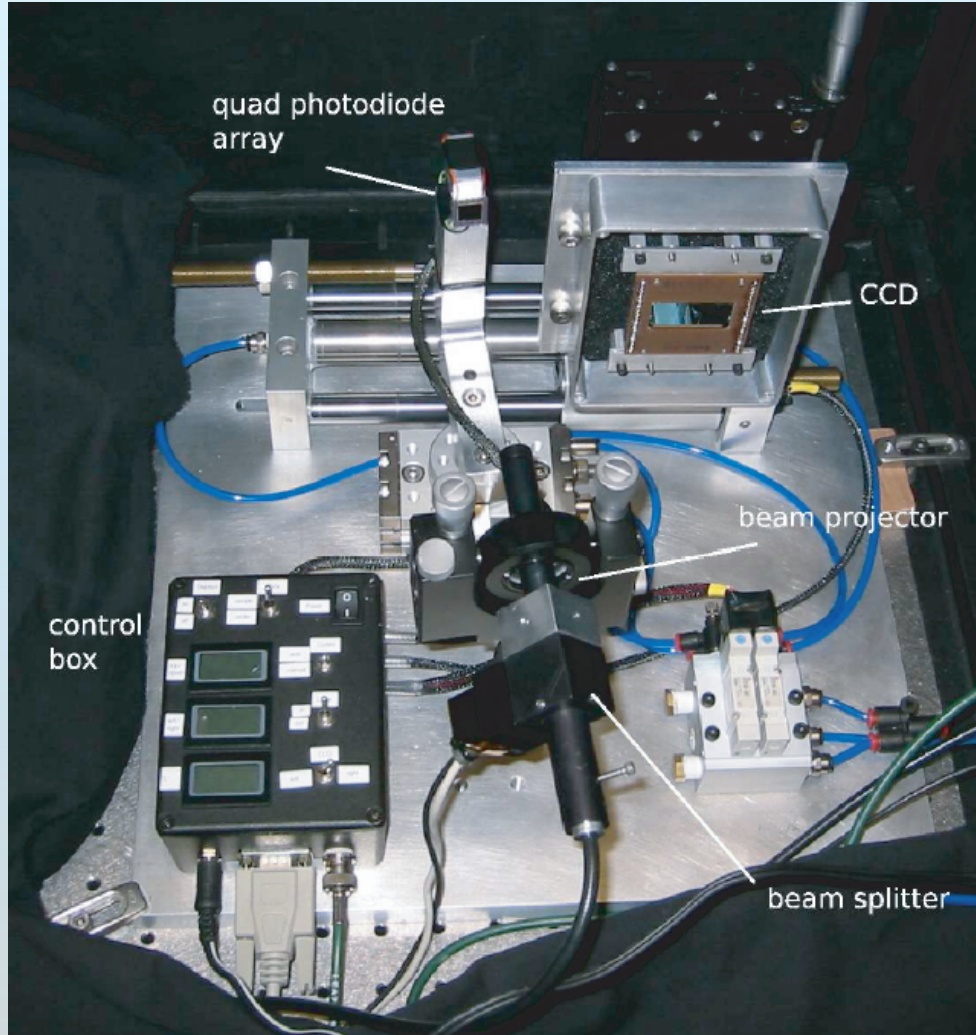
Jens Steckert's diplomathesis; for all practical purposes built by Jens under Armin Karcher's supervision

... and then the reflectometer. **THIS IS AN ABSOLUTE MEASUREMENT**

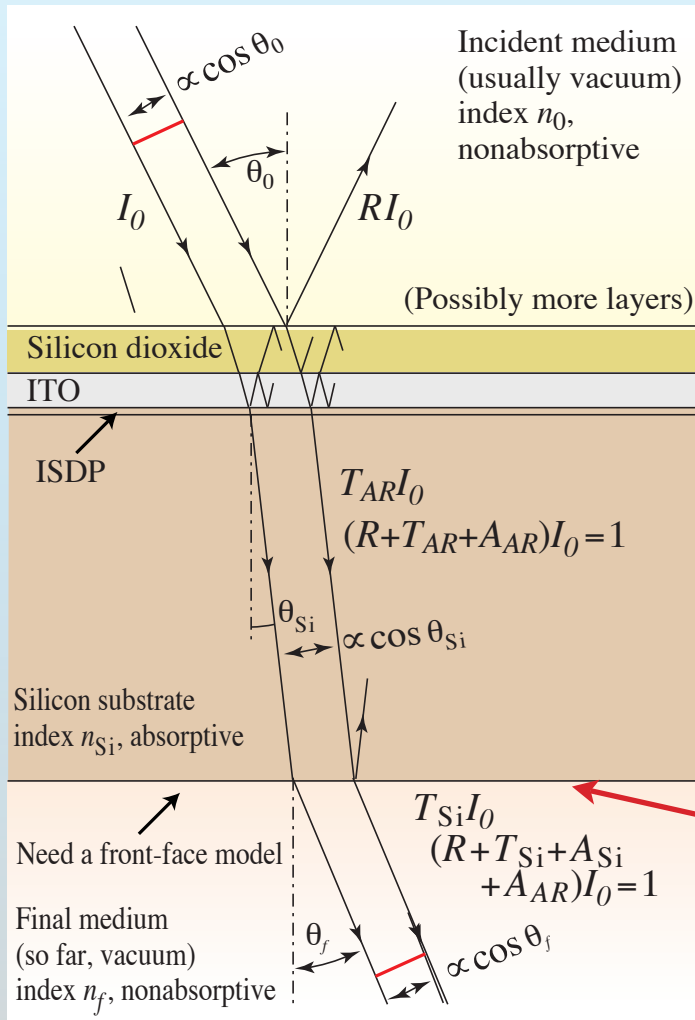


**Maximilian Fabricius'** diplomathesis; for all practical purposes built by Maximilian under **Armin Karcher's** supervision

## The amazing air-powered action machine!



We've recently attempted to model a coated CCD better:  
 Calculate the reflectivity, transmission, and quantum efficiency of a CCD with (possibly) absorptive coatings.



Complication #1

Complication #2

Treat the CCD substrate as a "film," so as to calculate the absorbed fraction (= QE) and fringing

Goals:

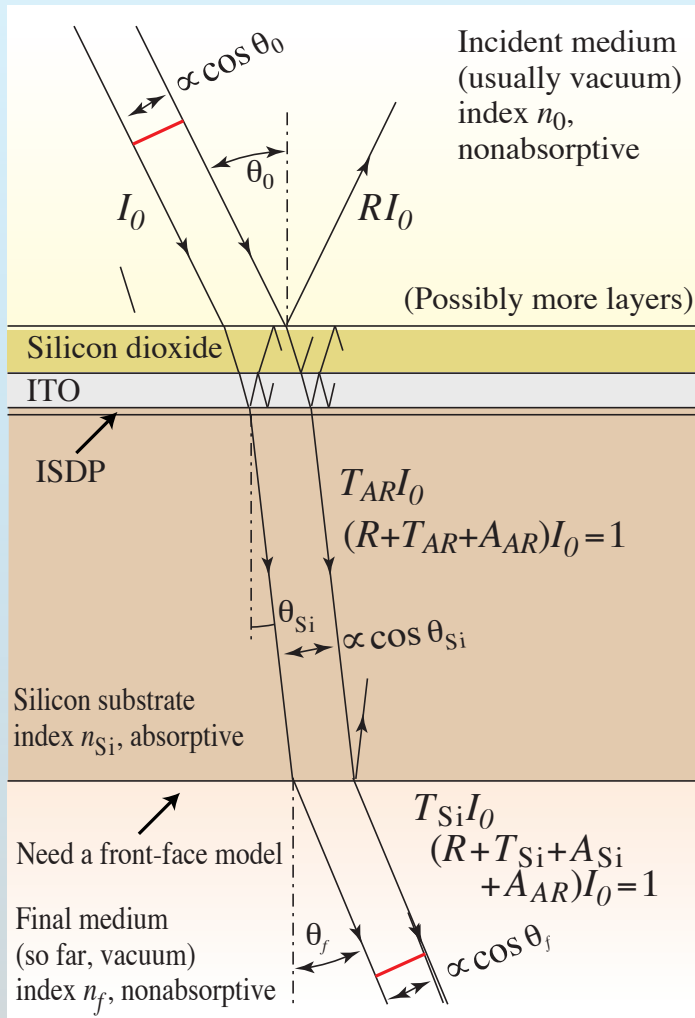
- \* Find an optimal antireflective coating (maximize QE)
- \* Understand absorption in the different films
- \* Sort out reflection from QE and photons lost elsewhere

Complication #3: Front-surface boundary conditions

Apology: Why didn't I just use a commercial package?

In what remains of my 15 min, all I can do is show some results.

I'll specialize to the LBNL CCD, since it has two absorptive layers (besides the substrate). **But code is general.**



← One of our problems is the in-situ doped polysilicon (ISDP) backside contact. It was difficult to find the appropriate complex index of refraction.



The index of refraction is complex:

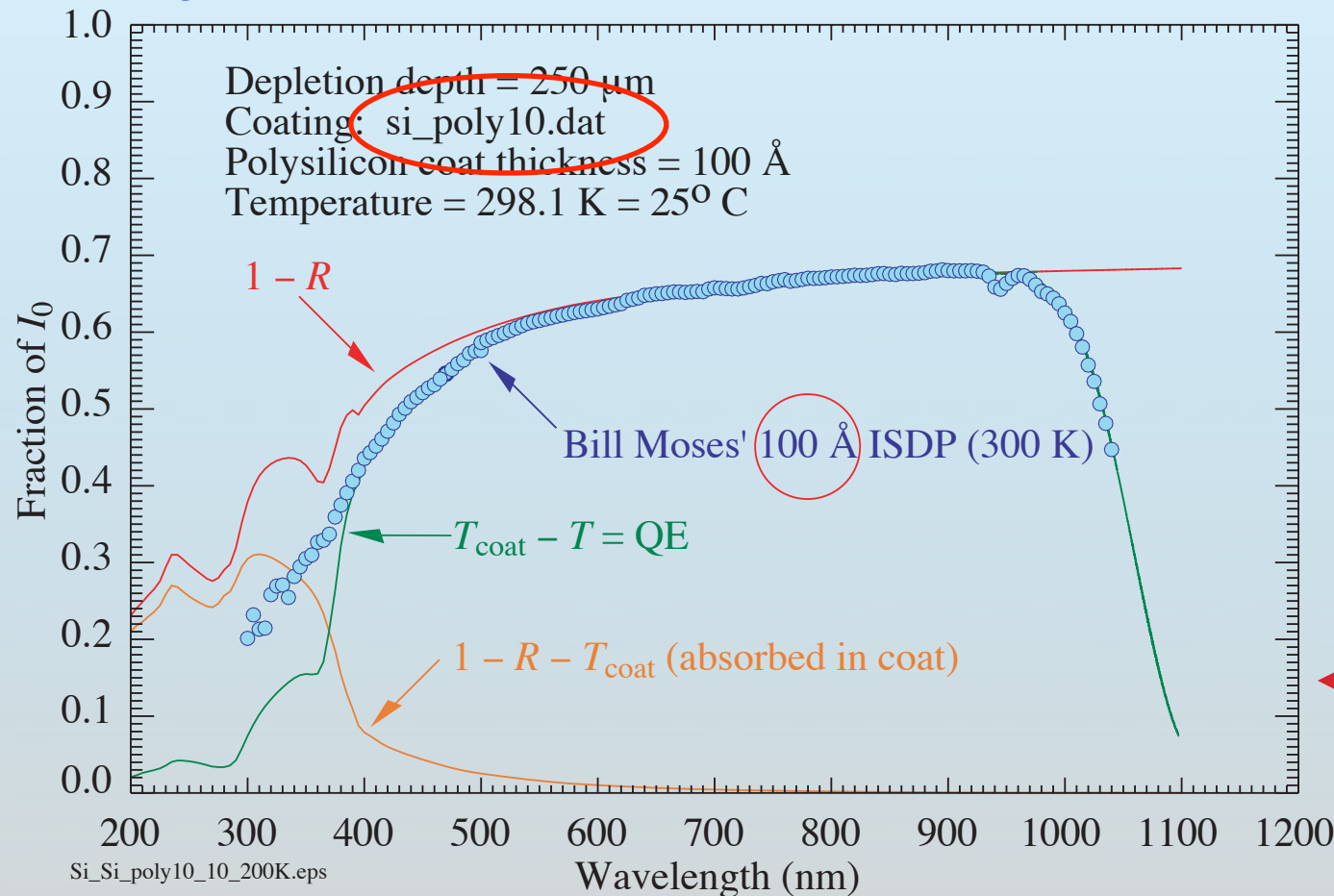
$$n_c = n - ik \quad (\ell_{\text{abs}} = \lambda/4\pi k)$$

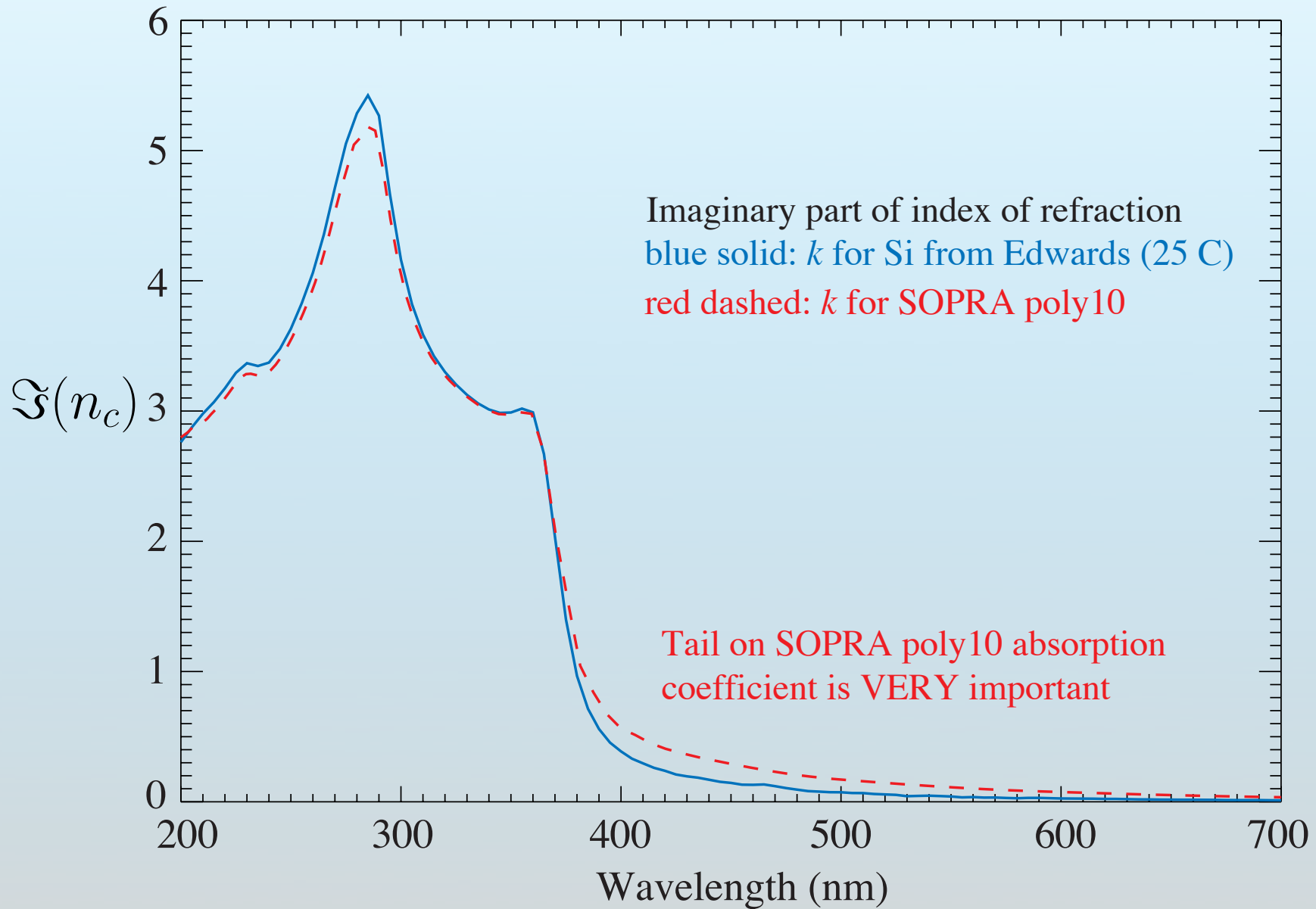
And sometimes hard to find. In addition to the usual literature, the SOPRA database is a gold mine.

We were lucky enough to have old data from Bill Moses (LBNL), who made a systematic study of the effect of ISDP thickness on photodiode quantum efficiency.

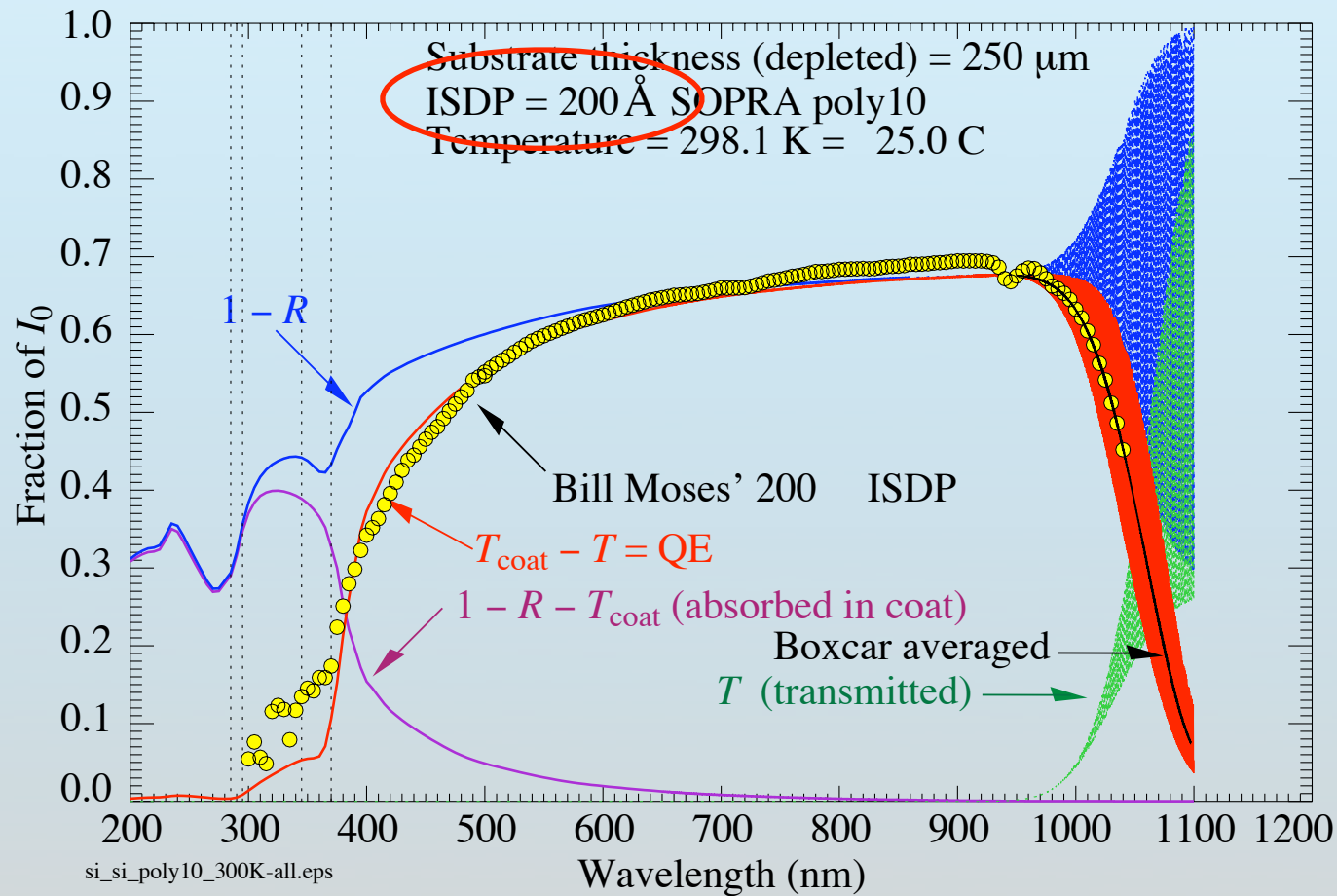
Of the 13 candidate SOPRA tables, “SIPOLY10.NK” provided the best description of the Moses data.

← Naked Si with ISDP coat, on diode at 300K

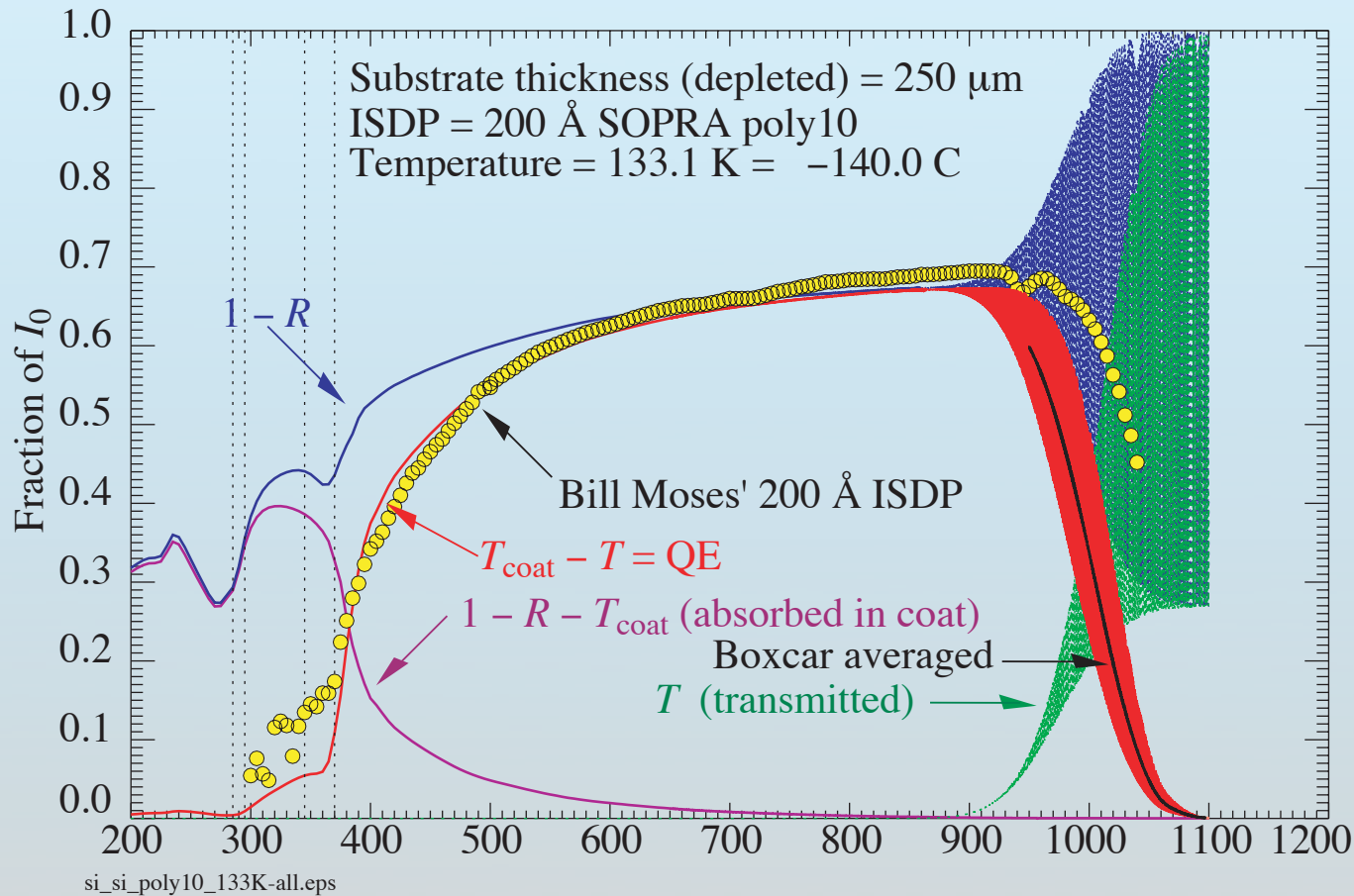




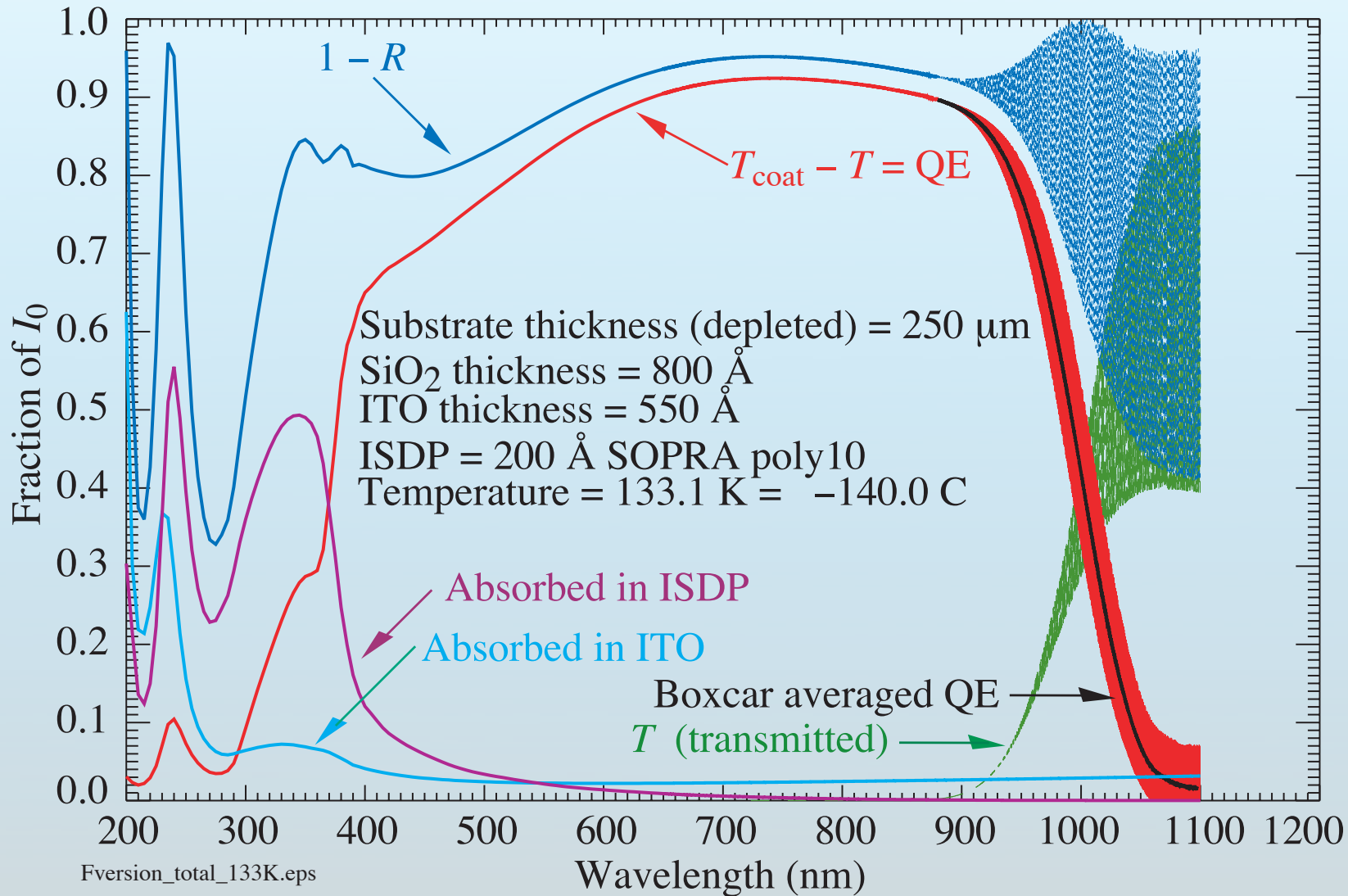
The full calculation looks like this:



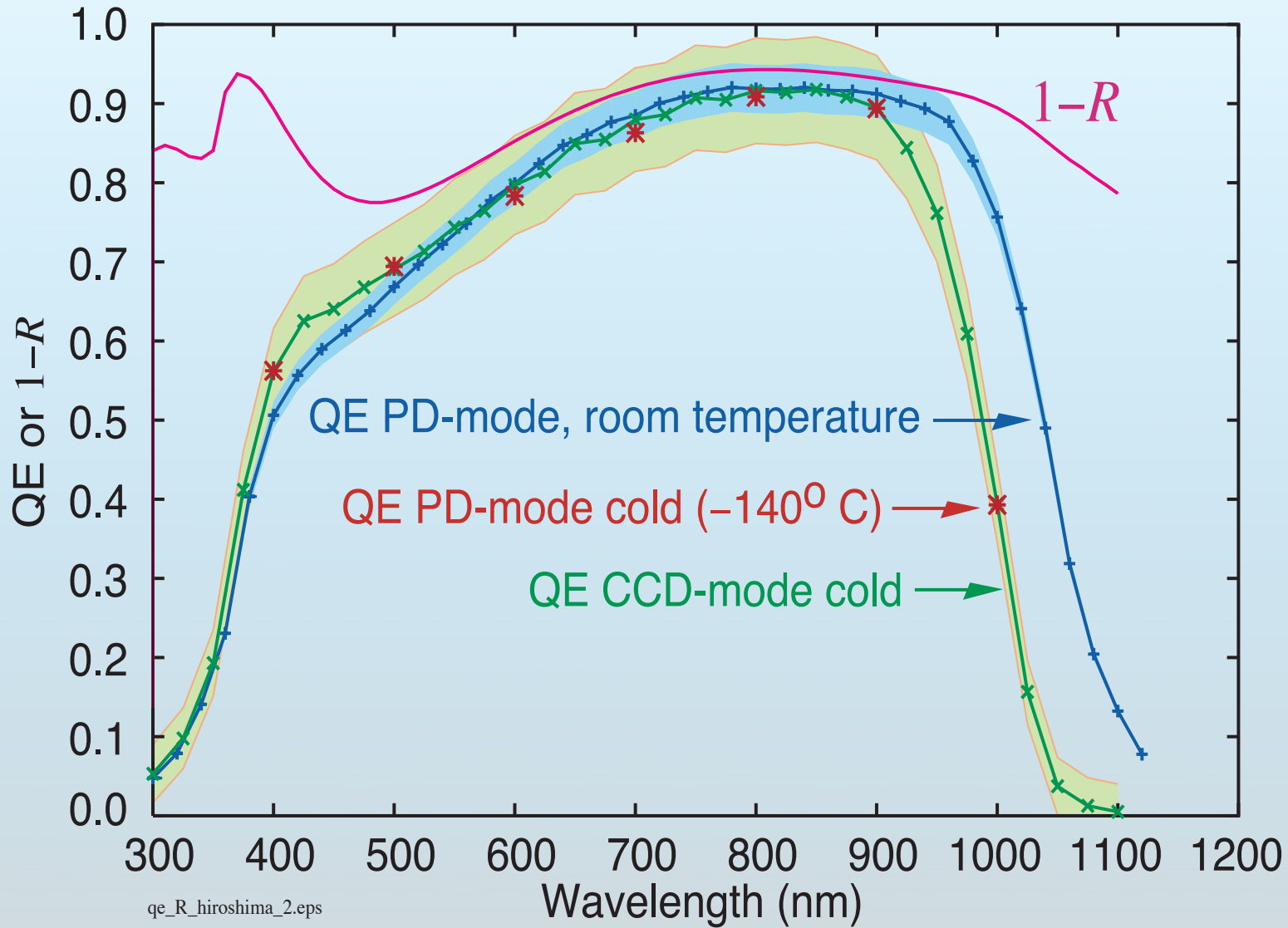
(Side lesson: cooling is hard on the red response)



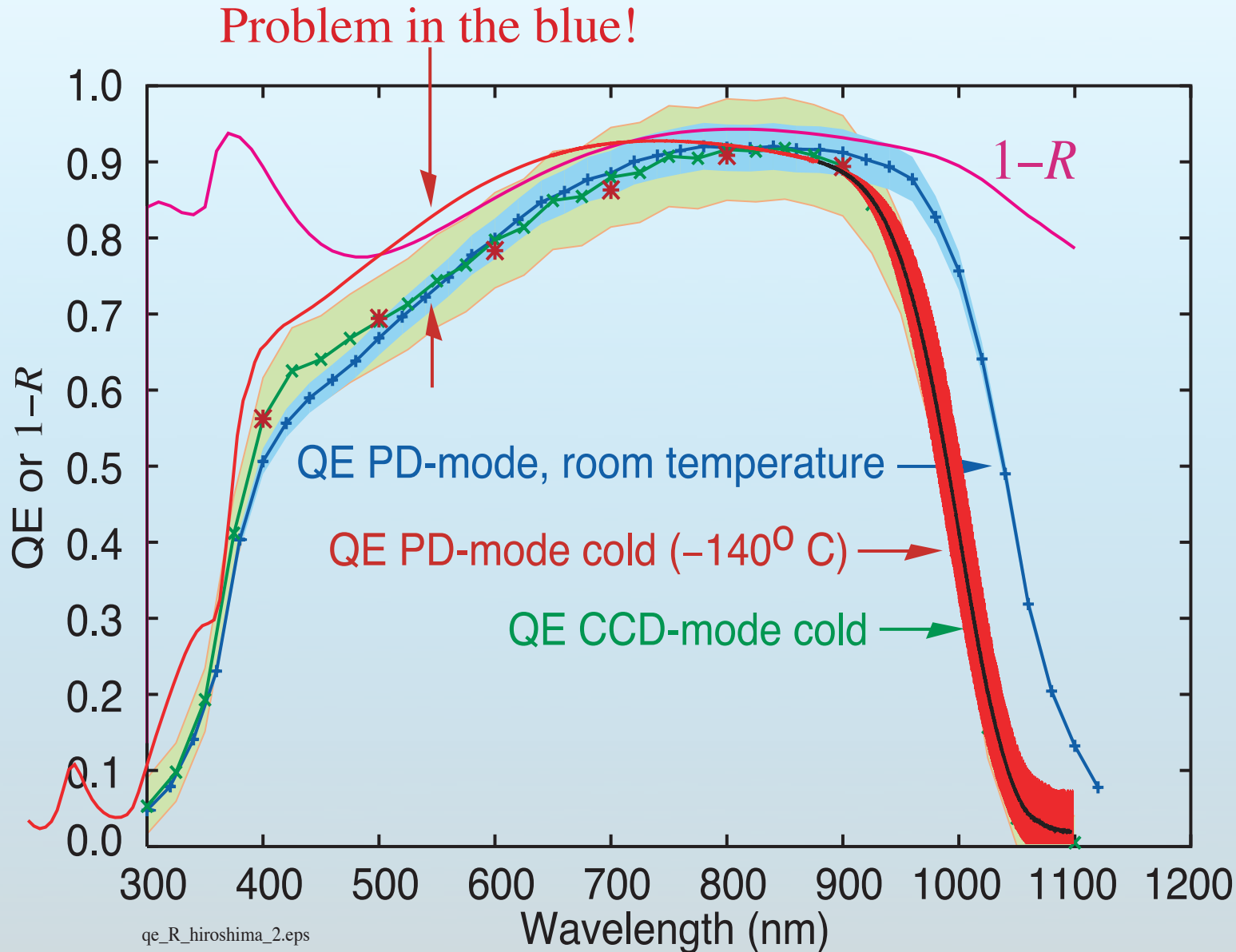
## Realistic modeling of the present SNAP CCDs



Difference between  $1 - R$  and “central” QE is absorption in the ITO!

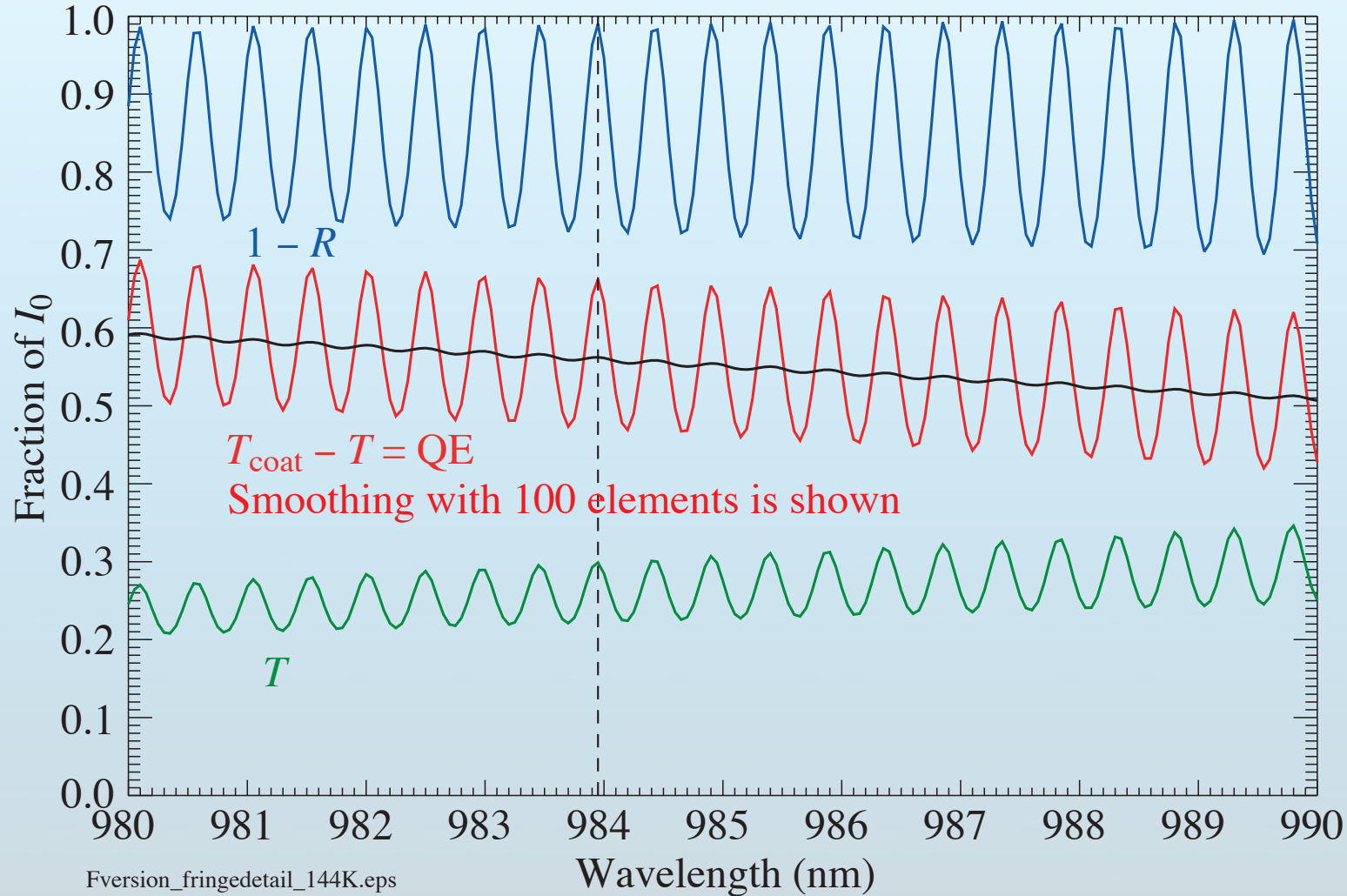


Actual measurements by Maximilion Fabricius



An earlier AR coating recipe had worked fine; here there were also problems with condensation onto the CCD. We take this failure as diagnostic rather than as a problem with the modeling

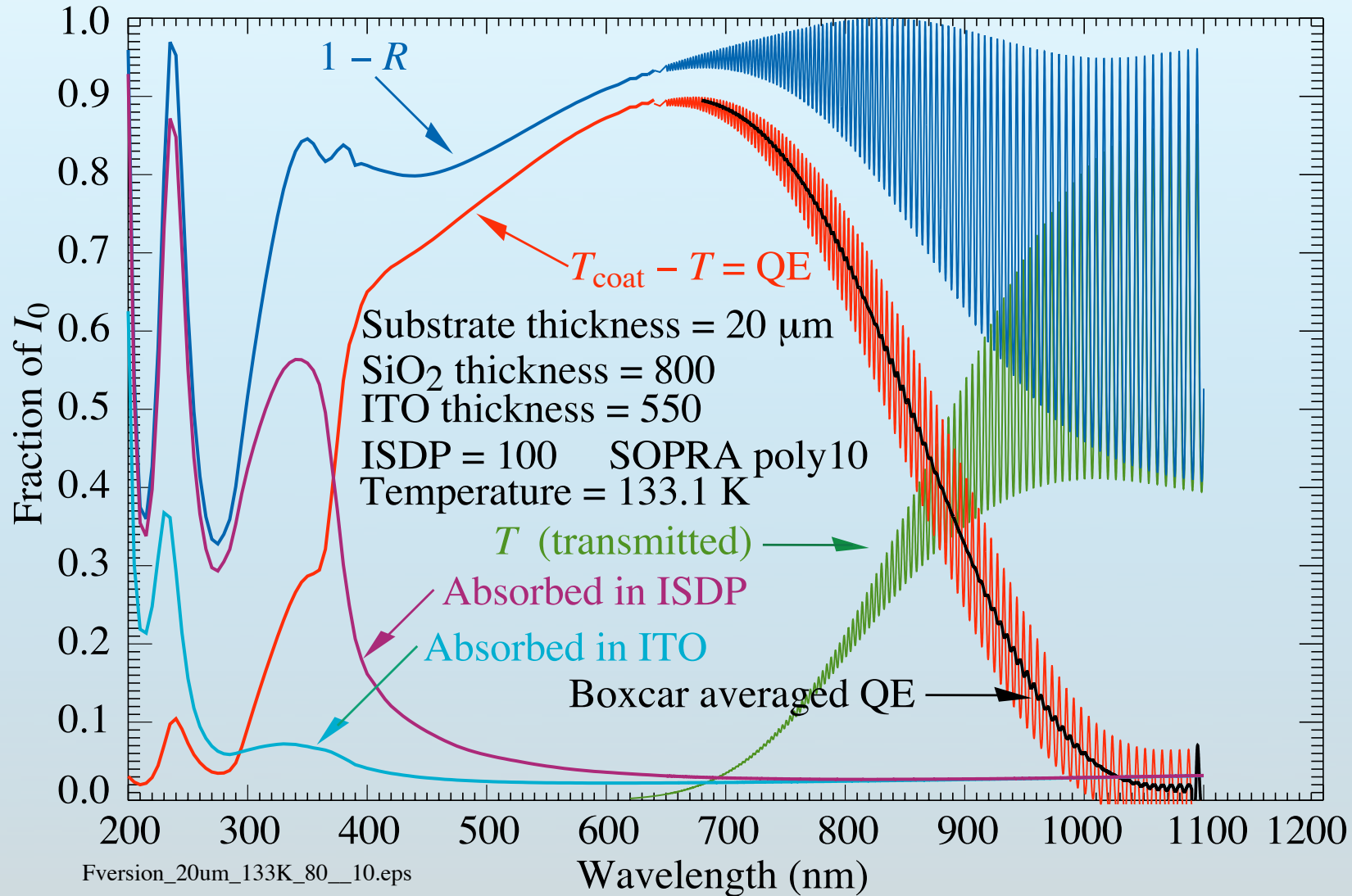
## Fringe region detail



Note “conspiracy” of reflection and transmission to make the fringes less violent!

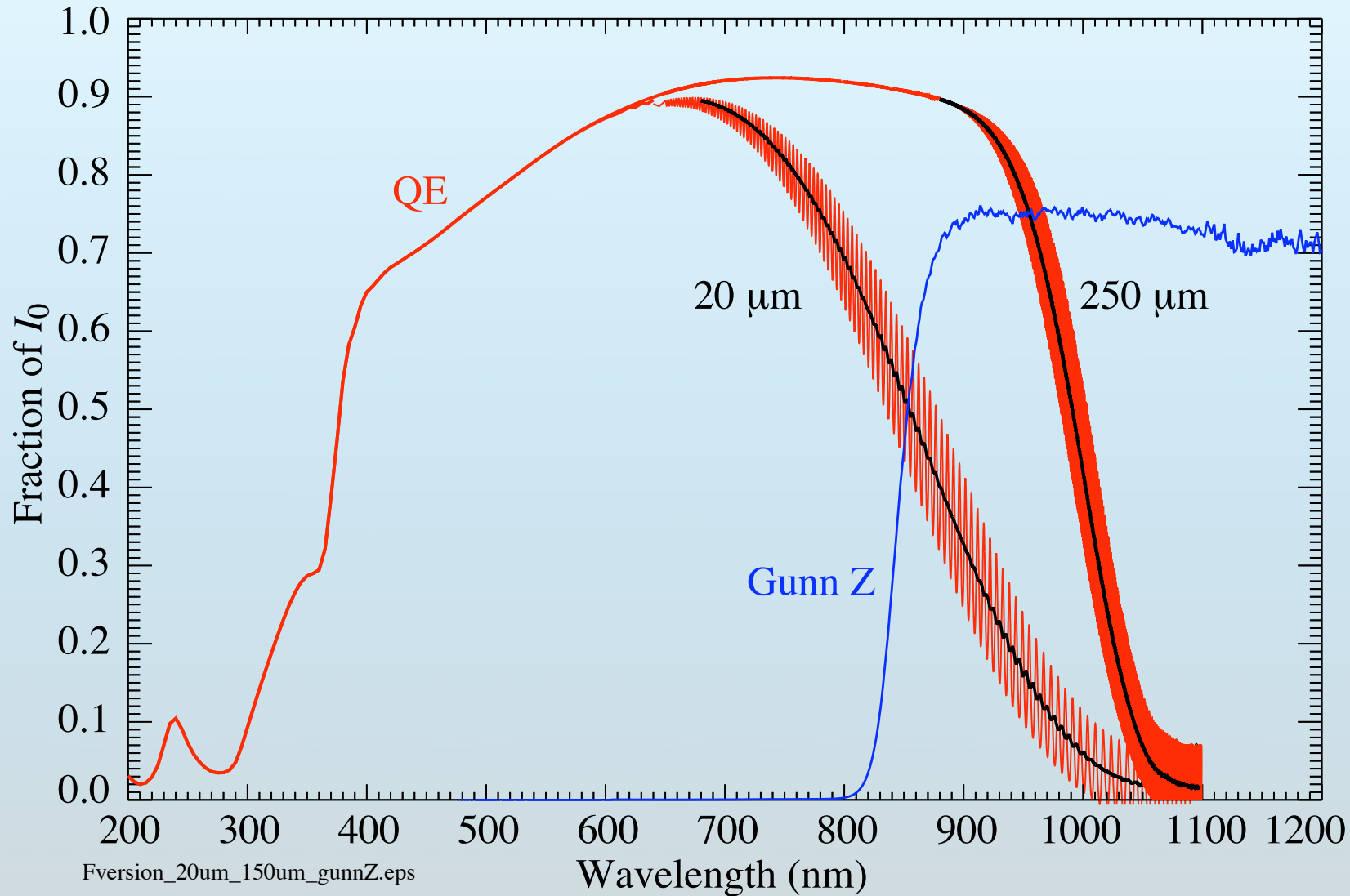


## Calculation for a traditional thinned CCD:



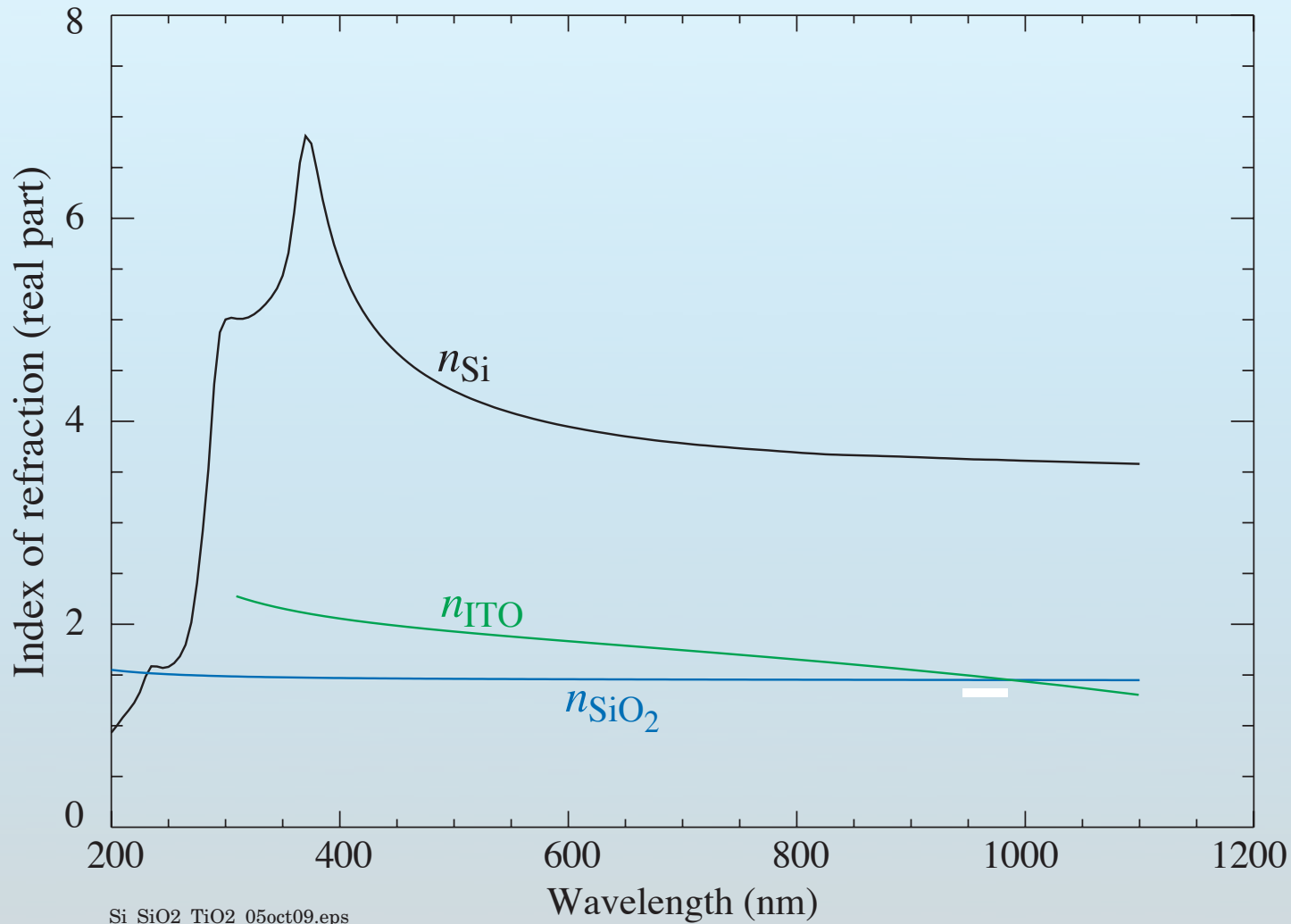
Shows widely spaced fringes extending to below 700 nm.

## Thin and thick compared to Gunn Z filter bandpass



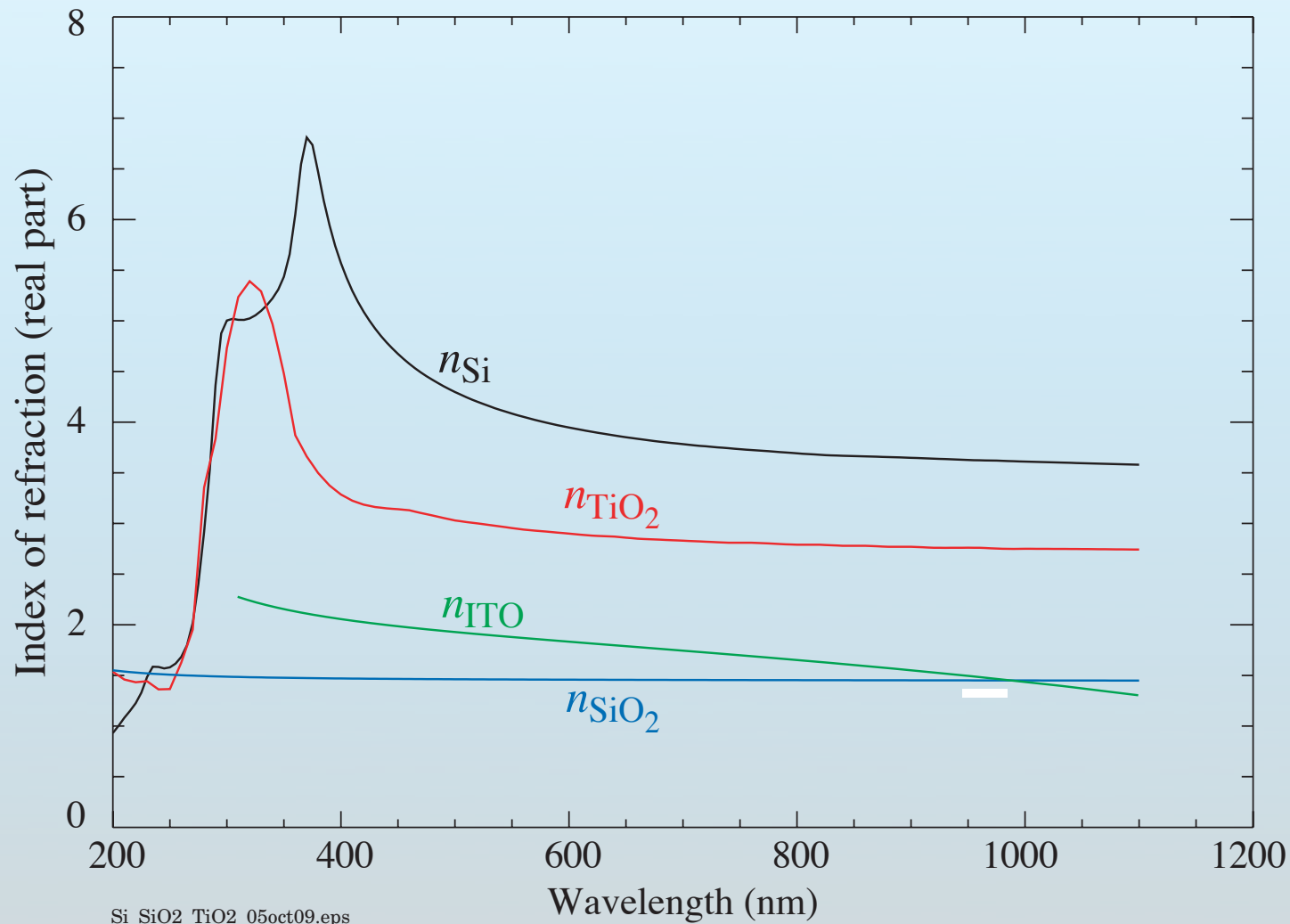
Spacing of fringes:  $\delta\lambda = \lambda^2 / 2nd$

It is surprising at first that the thickness of ITO and SiO<sub>2</sub> films can be adjusted to get such good response

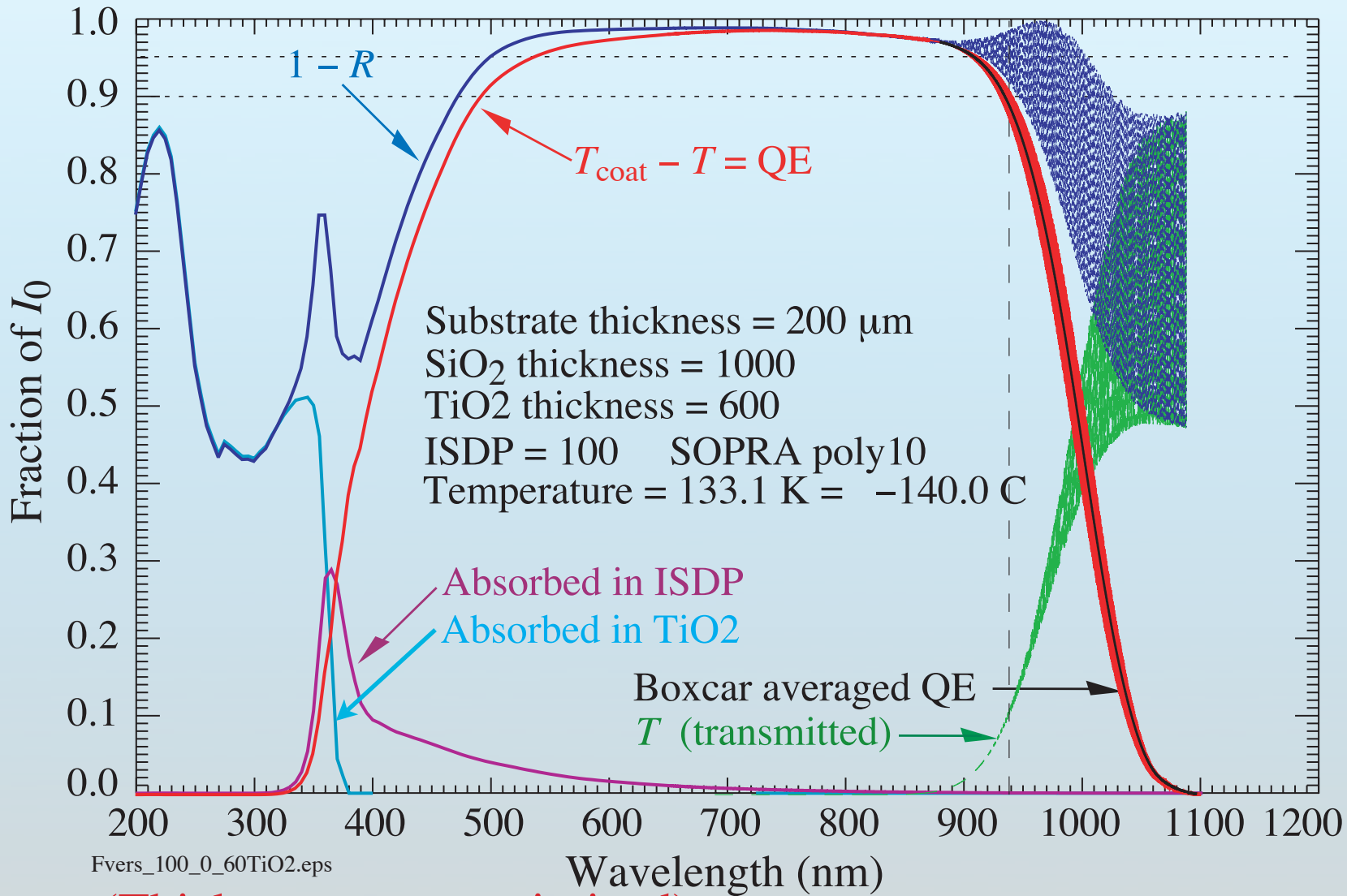


... and the ITO index shape doesn't track that of Si very well.

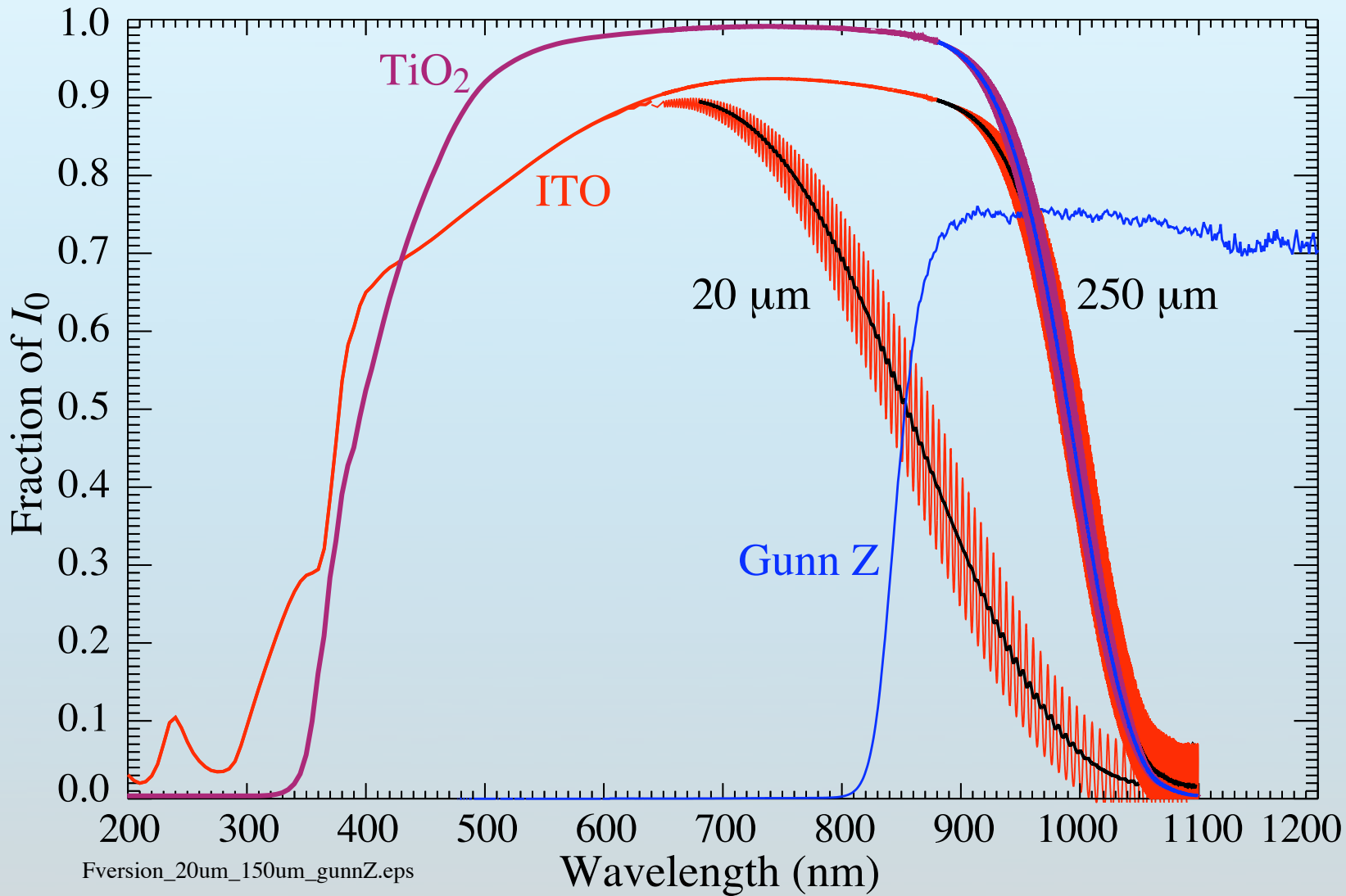
Roger Smith recently told us about the miracle coating,  $\text{TiO}_2$ :



This time the tracking of the Si index is quite respectable!

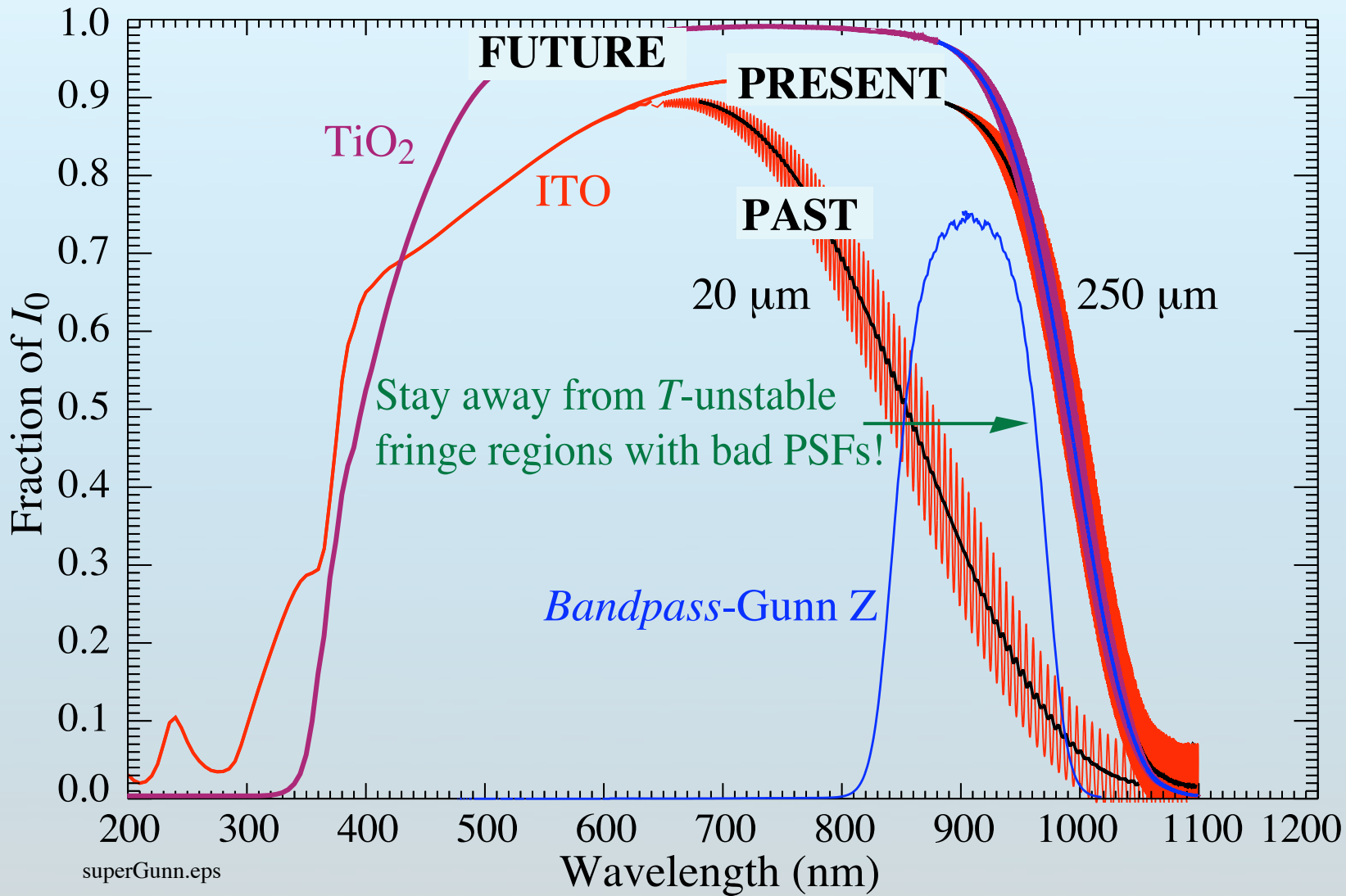


(Thicknesses not optimized)



Fversion\_20um\_150um\_gunnZ.eps

... and this is a good place to stop!





SPARE SLIDES FOLLOW

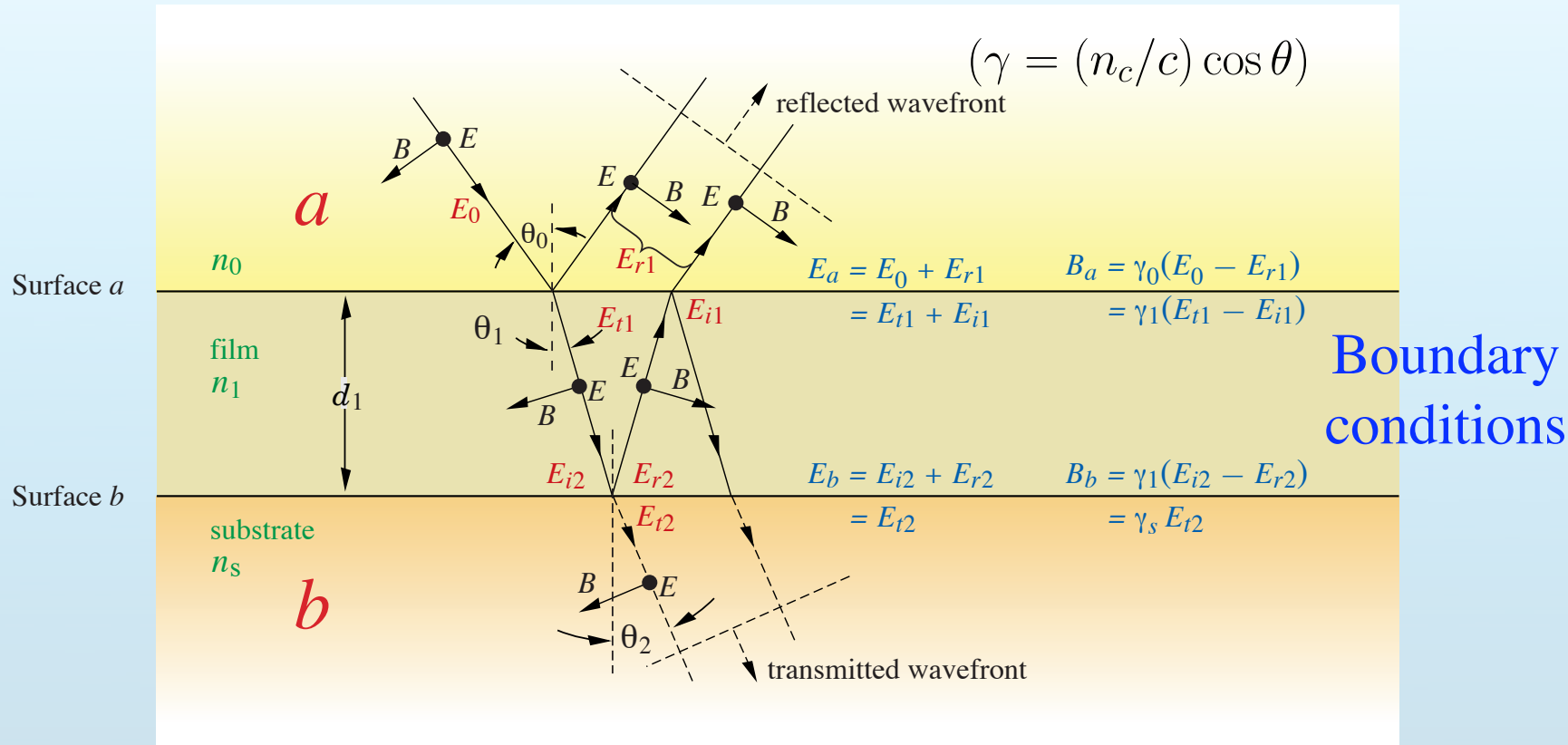




$n_c$  is the **complex** index of refraction in a single transit of the  $j$ th film:

$$n_c = n - ik \quad (\ell_{\text{abs}} = \lambda/4\pi k)$$

(The sign convention for the absorptive part is not the same in all books-- and has been changed since my previous calculations!)



The approach is standard: multiple reflection is taken care of by treating the transmission/reflection at an interface as a boundary condition problem. For normal incidence on a single film,  $E$  and  $B$  on entry and exit are related by

$$\begin{pmatrix} E_a \\ B_a \end{pmatrix} = \begin{pmatrix} \cos \delta_1 & \frac{i \sin \delta_1}{n_{c1}/c} \\ i (n_{c1}/c) \sin \delta_1 & \cos \delta_1 \end{pmatrix} \begin{pmatrix} E_b \\ B_b \end{pmatrix} \equiv M_1 \begin{pmatrix} E_b \\ B_b \end{pmatrix}$$

$$\begin{pmatrix} E_a \\ B_a \end{pmatrix} = \begin{pmatrix} \cos \delta_1 & \frac{i \sin \delta_1}{n_{c1}/c} \\ i (n_{c1}/c) \sin \delta_1 & \cos \delta_1 \end{pmatrix} \begin{pmatrix} E_b \\ B_b \end{pmatrix} \equiv \boxed{M_1} \begin{pmatrix} E_b \\ B_b \end{pmatrix}$$

$\delta_j$  is the **complex** phase change in a single transit of the  $j$ th film:

$$\delta_j = (d_j/\lambda)n_{cj} = \delta_{Rj} + i\delta_{Ij} \quad \leftarrow \text{Note that } \delta_I \text{ is negative!}$$

If there are  $N$  films, we just multiply the transfer matrices:

$$\begin{pmatrix} E_a \\ B_a \end{pmatrix} = M_1 M_2 \dots M_N \begin{pmatrix} E_b \\ B_b \end{pmatrix} \equiv M \begin{pmatrix} E_b \\ B_b \end{pmatrix}$$

So: light with amplitude  $I$  is incident on film from medium with  $n_0$  (real for initially incident light)

It is reflected (amplitude  $r$ ) and transmitted (amplitude  $t$ ) by the film, emerging into a substrate with index  $n_s$  (also generally complex)

$$r = \frac{(n_0 m_{11} + n_0 n_s m_{12}) - (m_{21} + n_s m_{22})}{(n_0 m_{11} + n_0 n_s m_{12}) + (m_{21} + n_s m_{22})} \implies R = n_0 |r|^2$$

$$t = \frac{2n_0}{(n_0 m_{11} + n_0 n_s m_{12}) + (m_{21} + n_s m_{22})} \implies T = n_s |t|^2$$



$m$  is the product of all the relevant transfer matrices

There's one more nuance not usually encountered in normal thin film analysis: **What if  $e^{-\delta_I}$  overflows the computer?** (Remember that it is negative, and for blue light in the substrate it can be hundreds of thousands)

$$\begin{aligned}\cos \delta &= \cos \delta_R \cos i\delta_I - \sin \delta_R \sin i\delta_I \\ &= \cos \delta_R \cosh \delta_I - i \sin \delta_R \sinh \delta_I \\ &= e^{-\delta_I} \frac{1}{2} [\cos \delta_R (1 + e^{2\delta_I}) + i \sin \delta_R (1 - e^{2\delta_I})] \\ &\equiv e^{-\delta_I} \text{FCOS}(\delta_R, \delta_I)\end{aligned}$$

And similarly for  $\sin \delta$ . So replace  $\delta_{Ij}$  with -10 for  $\delta_{Ij} < -10$  and write factored matrices:

$$\mathcal{M}_j \equiv e^{-\delta_{Ij}} \mathcal{M}_j^F$$

Then

$$r = \frac{(n_0 m_{11}^F + n_0 n_s m_{12}^F) - (m_{21}^F + n_s m_{22}^F)}{(n_0 m_{11}^F + n_0 n_s m_{12}^F) + (m_{21}^F + n_s m_{22}^F)}$$

← Absorptive substrate doesn't affect reflection

$$t = \frac{2n_0 \exp(\sum \delta_{Ij})}{(n_0 m_{11}^F + n_0 n_s m_{12}^F) + (m_{21}^F + n_s m_{22}^F)}$$

← If there's a really absorptive substrate, no transmission

For wavelengths less than about 900 nm, there IS no reflection from the “front” surface!

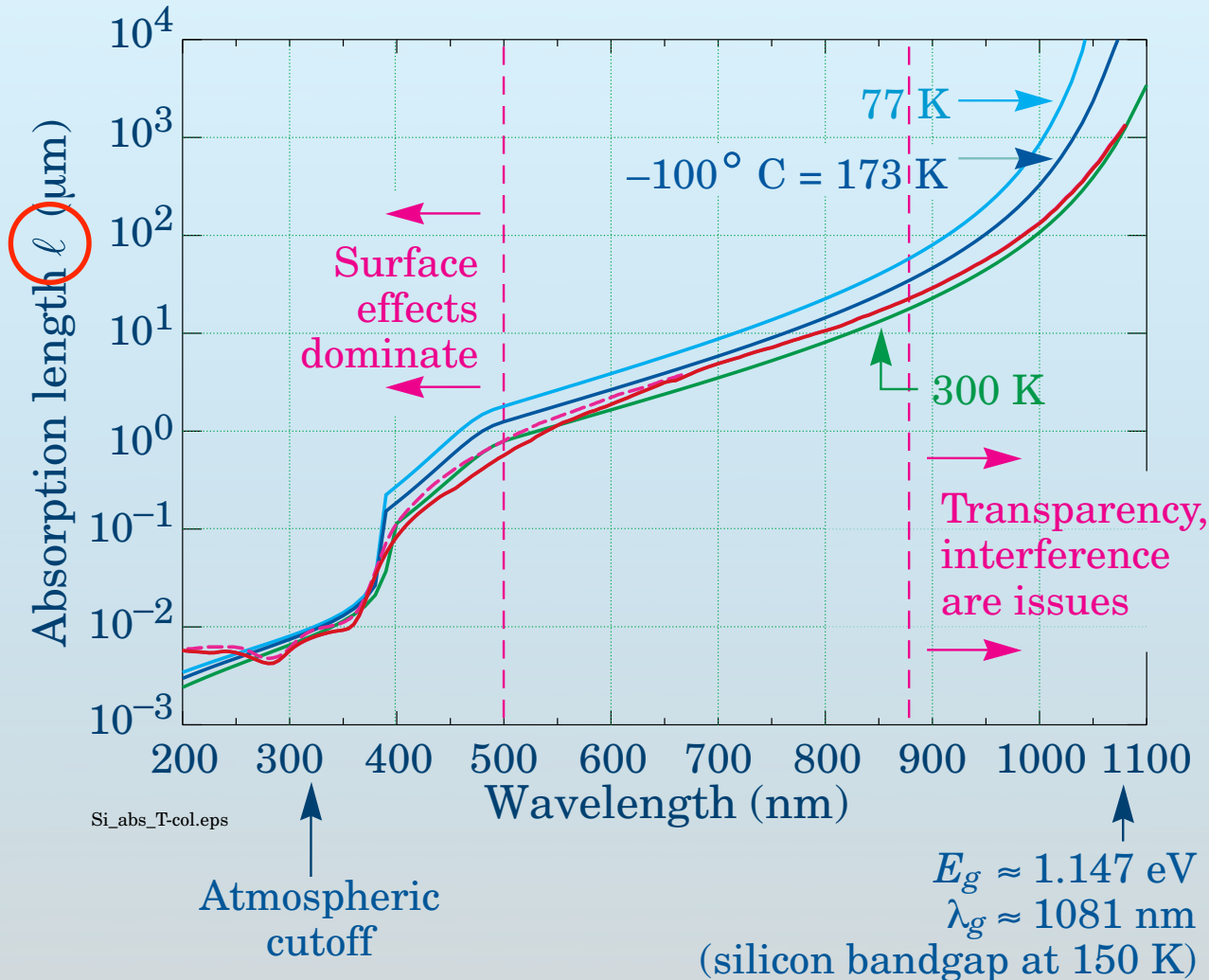
And there is very little reflection from the ITO-ISDP interface at any wavelength (zero for  $> 400$  nm, 0.07 at 350 nm).

So: 
$$\begin{pmatrix} E_a \\ B_a \end{pmatrix} = M_{AR} \begin{pmatrix} E_{bAR} \\ B_{bAR} \end{pmatrix}$$
 Added later:  
Maybe that should be 0.07%

1. Let  $M_{AR} = M_{SiO_2}M_{ITO}$ ; calculate  $R$  and  $T$  with a Si substrate.
2. Let  $M_{AR} = M_{SiO_2}M_{ITO}M_{ISDP}$ ; calculate  $R$  and  $T$  with a Si substrate.
3. For the complete CCD, calculate  $R$  and  $T$  with an AIR substrate.

$\Rightarrow$  Subtract appropriately to find absorption in ITO, ISDP, and Si (=QE)

$$n_c = n - ik, \quad k = \lambda/4\pi\ell$$



Red is from Janesick and tabulated  $n$  and  $k$  for silicon. Note inflections at short wavelengths.

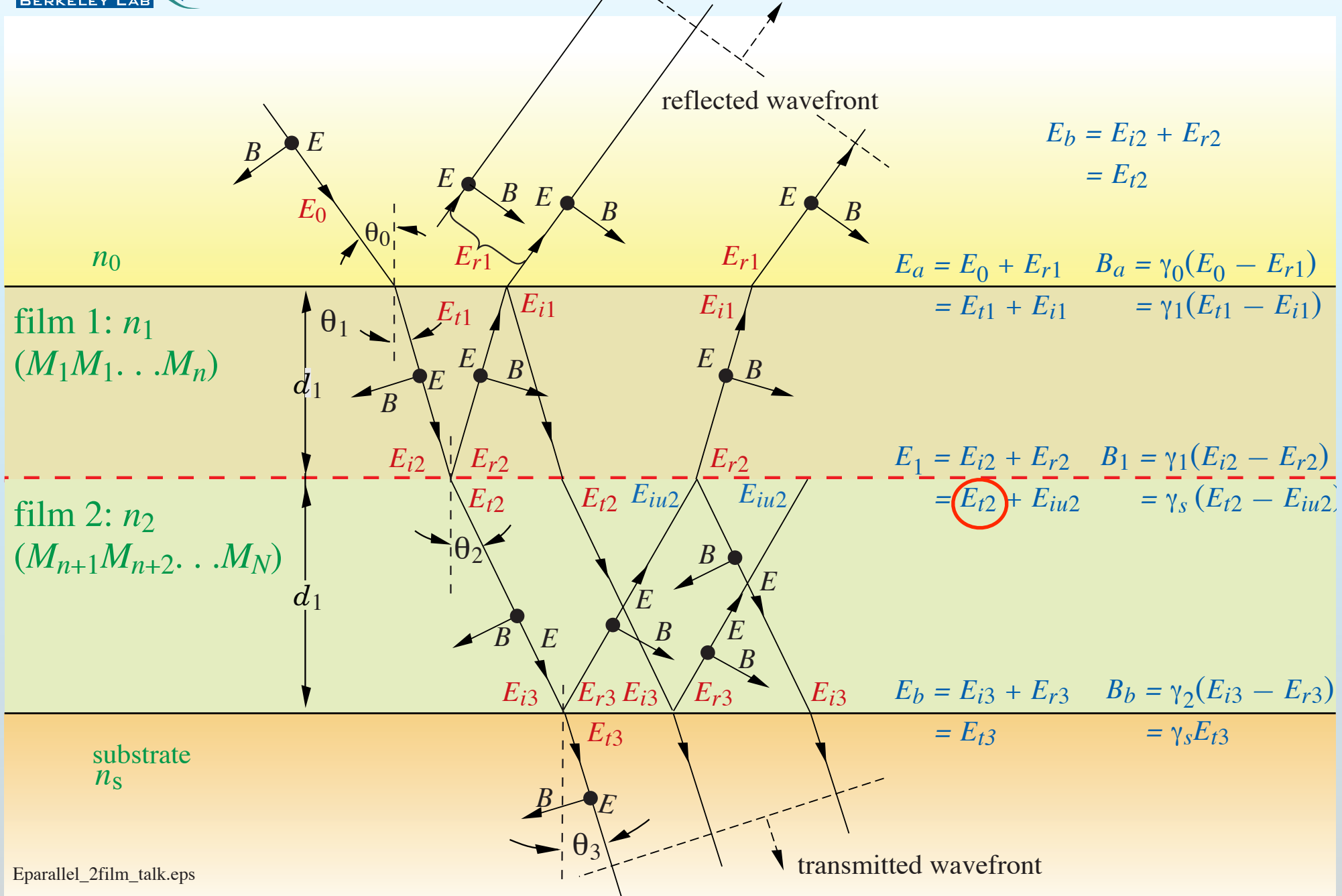
$T$  dependent curves from Rajkanan, Singh, and Shewchun. Note monotonic behavior, unlike the tabulated case.





So in contrast to previous modeling:

- ☺ Results at the blue end ( $< 500$  nm) can be trusted somewhat, since the Si + ISDP (SOPRA poly10) results agree with Bill Moses' measurements (diodes)
- ☺ Absorption in the ITO and ISDP are clearly separated, at least for wavelengths  $< 900$  nm
- ☹ There is a formal problem in the separation, especially important at wavelengths  $> 900$  nm. **Before proceeding, I would like to try to solve that problem**





$$(\gamma = (n_c/c) \cos \theta)$$

The phase shift  $\Delta$  as the light goes through the film once is  $nc(2\pi/\lambda)$   
 $nc = n - i k$

Given all those complex indices, I wanted to sort through Maxwell's equations to see how it all worked.

Example: the intensity  $I$ , the magnitude of the Poynting vector, is

$$I \propto \text{Re}(E^*B) \propto \text{Re}(nc EE^*) \\ \propto n EE^*$$

Is that the real part of  $nc$  or  $\text{Im}(nc)$ ??

Turns out to be real part.

$$I \propto \Re(E^* B) \propto \Re(n_c E E^*) \propto n E E^*$$

Is that  $|n_c|$  or  $\Re(n_c)$ ??

→ Turns out to be real part.

$n_c$  is the **complex** index of refraction in a single transit of the  $j$ th film:

